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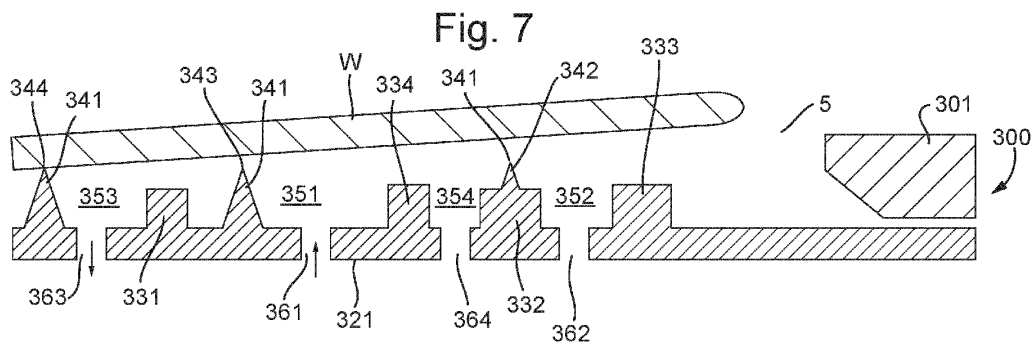
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(54) Title: SUBSTRATE SUPPORT AND LITHOGRAPHIC APPARATUS



(57) Abstract: A substrate support configured to support a substrate in a lithographic apparatus comprising: a first circumferential wall; a first opening radially outwards of the first circumferential wall and configured to supply and/or extract gas; a second circumferential wall radially outwards of the first opening; a second opening in fluid communication with ambient pressure and radially outwards of the second circumferential wall; a third circumferential wall radially outwards of the second opening; a third opening radially outwards of the third circumferential wall and configured to extract fluid; and a fourth circumferential wall radially outwards of the third opening.

WO 2023/241893 A1